

WHAT IS CLAIMED IS:

1. A method of manufacturing an envelope which includes a first substrate, a second substrate opposed to the first substrate, and a space defining member which is located between the first substrate and the second substrate and has a substantially plate shape, the method comprising:
 - applying a tension to the space defining member;
 - fixing the space defining member to which the tension is applied to the first substrate; and
 - releasing the tension from the space defining member fixed to the first substrate,
wherein in the fixing of the space defining member to the first substrate, a fixing point of the space defining member to the first substrate is located between points at which the tension is exerted.
2. A method of manufacturing an envelope according to claim 1, wherein in the applying of the tension to the interval specifying member, a base of the spacing defining member is located at the point at which the tension is exerted.
3. A method of manufacturing an envelope according to claim 1, wherein in the applying of the

tension to the spacing defining member, an auxiliary support member connected with a base of the space defining member is located at the point at which of the tension is exerted.

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4. A method of manufacturing an electron beam apparatus which includes a first substrate having a plurality of electron-emitting devices on a surface thereof, a second substrate which is opposed to the 10 first substrate and in which an electrode that controls electrons emitted from the plurality of electron-emitting devices is formed, and at least one space defining member which is located between the first substrate and the second substrate and has a 15 substantially plate shape, the method comprising:

applying a tension to the space defining member;

fixing the space defining member to which the tension is applied to the first substrate; and

20 releasing the tension from the space defining member fixed to the first substrate,

wherein in the fixing of the spacing defining member to the first substrate, a fixing point of the space defining member to the first substrate is 25 located between points at which the tension is exerted.

5. A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member, a base of the space defining member is located at the 5 points at which the tension is exerted.

6. A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member, 10 an auxiliary support member connected with a base of the space defining member is located at the point at which the tension is exerted.

7. A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member, 15 the tension is applied by a spacer conveying unit.

8. A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member, 20 the tension is applied by a tension applying unit.

9. A method of manufacturing an electron beam apparatus according to claim 4, wherein the interval 25 specifying member has a base of an insulating property.

10. A method of manufacturing an electron beam apparatus according to claim 4, wherein the space defining member has a surface on which a high resistance film is formed.

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11. A method of manufacturing an electron beam apparatus according to claim 10, wherein the high resistance film has a sheet resistance of 10^7 [Ω/square] or more and 10^{14} [Ω/square] or less.

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12. A method of manufacturing an electron beam apparatus according to claim 4, wherein the first substrate further includes a plurality of wirings that electrically connect the plurality of electron-emitting devices and the interval specifying members are located on the wiring.

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